

Abstract

The present invention relates to a device (10) for cleaning
pot-shaped hollow bodies (12), in particular transport con-
5 tainers (30) for semiconductor wafers or for EUV lithography
masks, wherein the device (10) comprises a support wall (20)
on which the marginal surface (38) of the hollow body (12) can
be placed; a locking device (26) by which the hollow body (12)
is sealingly connectable to the marginal surface (48) and re-
10 leasably connectable to the support wall (20); and at least
one passage opening (24) that is formed by the support wall
(20) and that is arranged radially within the locking device
(26); a cleaning device (40) by which a first cleaning fluid
for cleaning the inner hollow body surface (33) can be dis-
15 pensed when the hollow body (12) is connected to the support
wall (20); and a first drainage channel (70) having a first
end (72), wherein the first end (72) of the first drainage
channel (74) is only in fluid communication with the passage
opening (24) and by which the first cleaning fluid dispensed
20 by the cleaning device (40) can be drained.

[Figure 1.]